L Number	Hits	Search Text	DB	Time stamp
1	161	(antireflection or antireflective or	USPAT;	2004/10/21 14:58
		anti-reflection or anti-reflective or arc or	US-PGPUB;	
		arl) same (particle or particulate or	EPO; JPO;	
		nanoparticle or microparticle) near10	DERWENT;	
		(binder or matrix or resin or polymer) and	IBM_TDB	
		(photolithography or photolithographic or	_	
		photoresist or resist or photo-lithography		
		or photo-lithographic or photo-resist)		
2	14	•	USPAT	2004/10/21 14:12
		"4412903" "4530891" "4563407"		
		"4657648" "4696877" "4720442"		
		"4910122" "4942451" "5240554"		
_		"5302240" "5334486").PN.		
3	3	5744293.URPN.	USPAT	2004/10/21 14:17
4	9	(4	USPAT;	2004/10/21 15:00
		anti-reflection or anti-reflective or arc or	US-PGPUB;	
	!	arl) same (silicon adj dioxide or silicon	EPO; JPO;	
		adj oxide or sio or si adj o or titanium adj	DERWENT;	
		oxide or tio or ti adj o) near3 (binder or	IBM_TDB	
		matrix) same (particle or particulate or		
5	17	nanoparticles or microparticles) (antireflection or antireflective or	USPAT;	2004/10/21 15:11
ا	'	anti-reflection or anti-reflective or arc or	US-PGPUB;	2004/10/21 12:11
		arl) same (silicon adj dioxide or silicon	EPO; JPO;	
		adj oxide or sio or si adj o or titanium adj	DERWENT;	
		oxide or tio or ti adj o) near10 (binder or	IBM TDB	
		matrix) same (particle or particulate or	150,-155	
		nanoparticles or microparticles)		
6	40		USPAT;	2004/10/21 15:13
·		anti-reflection or anti-reflective or arc or	US-PGPUB;	2001, 20, 22 23.23
		arl) same (silicon near dioxide or silicon	EPO; JPO;	İ
		near oxide or sio or si adj o or titanium	DERWENT;	
		near oxide or tio or ti adj o) near10	IBM TDB	
		(binder or matrix)	_	
7	8	(US-6165657-\$ or US-6503689-\$ or	USPAT;	2004/10/21 15:26
		US-6569595-\$ or US-5750054-\$ or	US-PGPUB;	
		US-5948481-\$).did. or	JPO	
		(US-20030005956-\$).did. or (JP-09258459-\$ or		
		JP-08241858-\$).did.		
8	53	,	USPAT;	2004/10/21 15:28
		grain or micrograin or nanograin or	US-PGPUB;	1
		nanoparticle or microparticle)	JPO	
10	54		USPAT;	2004/10/21 15:31
		grain or micrograin or nanograin or	US-PGPUB;	
		nanoparticle or microparticle) and (silicon	JPO	
		near oxide or silicon near dioxide or si		
		near o or sio or titanium near oxide or ti near o or tio or silica or titania)		
11	67	·	USPAT;	2004/10/21 15:35
		or grain or micrograin or nanograin or	US-PGPUB;	2004/10/21 13:35
		nanoparticle or microparticle) and (silicon	JPO	
		near oxide or silicon near dioxide or si	010	
		near o or sio or titanium near oxide or ti		
		near o or tio or silica or titania)		
12	29	438/952.ccls. and (particle or particulate	USPAT;	2004/10/21 15:36
		or grain or micrograin or nanograin or	US-PGPUB;	
		nanoparticle or microparticle) and (silicon	JPO ,	
		near oxide or silicon near dioxide or si		
		near o or sio or titanium near oxide or ti		
		near o or tio or silica or titania)		
14	43	257/437.ccls. and (particle or particulate	USPAT;	2004/10/21 15:38
ļ		or grain or micrograin or nanograin or	US-PGPUB;	
l		nanoparticle or microparticle) and (silicon	JPO	
		near oxide or silicon near dioxide or si		
		near o or sio or titanium near oxide or ti		
		near o or tio or silica or titania)		

15		DET/EDI ODO gala and (name also an	TIODAM.	2004/10/21 15 20
15	58	257/E21.029.ccls. and (particle or	USPAT;	2004/10/21 15:39
		particulate or grain or micrograin or	US-PGPUB;	
		nanograin or nanoparticle or microparticle)	JPO	
		and (silicon near oxide or silicon near		
	1	dioxide or si near o or sio or titanium near		
	ļ	oxide or ti near o or tio or silica or		
		titania)		0004/50/05 15 00
16	50	438/72.ccls. and (binder or matrix)	USPAT;	2004/10/21 15:39
			US-PGPUB;	
		100/00	JPO	0004/00/00 05 45
17	9	,	USPAT;	2004/10/21 15:41
		(grain or particle or nanoparticle or	US-PGPUB;	
		microparticle or nanograin or micrograin or	JPO	
		particulate)		
18	4	438/636.ccls. and (binder or matrix) same	USPAT;	2004/10/21 15:42
		(grain or particle or nanoparticle or	US-PGPUB;	
		microparticle or nanograin or micrograin or	JPO	[
		particulate)		
19	2	100,700.0000. 0110 (2011001 01 11001211) 001110	USPAT;	2004/10/21 15:42
		(grain or particle or nanoparticle or	US-PGPUB;	
		microparticle or nanograin or micrograin or	JPO	
1	_	particulate)		
20	8	,,,, (,,,,	USPAT;	2004/10/21 15:43
		(grain or particle or nanoparticle or	US-PGPUB;	
	ĺ	microparticle or nanograin or micrograin or	JPO	
	_	particulate)		
21	2	,,	USPAT;	2004/10/21 15:44
		same (grain or particle or nanoparticle or	US-PGPUB;	
ŀ		microparticle or nanograin or micrograin or	JPO	
		particulate)		
-	4628	(antireflection or antireflective or	USPAT;	2004/10/21 10:33
}		anti-reflection or anti-reflective or arc or	US-PGPUB;	
		arl) near10 (particle or particulate or	EPO; JPO;	
		nanoparticle or microparticle)	DERWENT;	
			IBM_TDB	
-	27	, (USPAT;	2004/10/21 13:51
	-	anti-reflection or anti-reflective or arc or	US-PGPUB;	
		arl) near10 (particle or particulate or	EPO; JPO;	
		nanoparticle or microparticle) near20	DERWENT;	
		(photolithography or photolithographic or	IBM_TDB	
	1	photoresist or resist or photo-lithography		
		or photo-lithographic or photo-resist)		L